

ABSTRACT

SUBSTRATE CLEANING DEVICE, SUBSTRATE CLEANING APPARATUS, METHOD
FOR MANUFACTURING CLEANED SUBSTRATE and SUBSTRATE PROCESSING
APPARATUS

5 A substrate cleaning device 1 includes a substrate holding unit 10 configured to hold
a substrate W, a first cleaning unit 11 having a first cleaning member 11a caused to come into
contact with a first surface WA of the substrate W held by the substrate holding unit 10 to
clean the first surface WA, a second cleaning unit 12 having a second cleaning member 12a
caused to come into contact with the first surface WA of the substrate W held by the substrate
10 holding unit 10 to clean the first surface WA, and a controller 50 configured to control the first
and second cleaning units 11, 12 so that, when any one of the first cleaning member 11a and
the second cleaning member 12a cleans the first surface WA of the substrate W held by the
substrate holding unit 10, the other cleaning member is at a position apart from the substrate
W held by the substrate holding unit 10.

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Figure 1